

Atty.
Dkt. No.

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Client Ref.

306399

P-0375.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: Ralph KURT et al.

Appln. No.: Not Assigned

Filing Date: October 17, 2003

Date: October 17, 2003

Page

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of

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Examiner: Not Assigned

Group Art Unit: Not Assigned

2857

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
D.R.	AR	2003/0095623	05/2003	SINGER et al.	378	34	
D.R.	BR	2002/0109828	08/2002	MOORS et al.	355	76	
	CR						
	DR						
	ER						
	FR						
	GR						
	HR						

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
D.R.	IR	EP 1223468	07/2002	European	KOSTER et al.			X	
	JR	EP 0987601	03/2000	European	KOMATSUDA et al.			X	
	KR	EP 1182510	02/2002	European	MOORS et al.			X	
D.R.	LR	WO 99/42904	08/1999	PCT	SHMAENOK			X	
	MR								
	NR								
	OR								
	PR								
	QR								
	RR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

D.R.	SR	EP Search Report for EP 02079329.5 dated August 22, 2003							
	TR	William Partlo et al., "Development of an EUV (13.5 nm) Light Source Employing a Dense Plasma Focus in Lithium Vapor," Proc. of SPIE, Vol. 3997, pgs. 136-156 (2000).							
	UR	Malcolm W. McGeoch, "Power Scaling of a Z-Pinch Extreme Ultraviolet Source," Proc. of SPIE, Vol. 3997, pgs. 861-866 (2000).							
D.R.	VR	Klaus Bergmann et al., "Highly Repetitive, Extreme-Ultraviolet Radiation Source Based on a Gas-Discharge Plasma," Applied Optics, Vol. 38, pgs. 5413-5417 (1999).							
	WR								
	XR								

Examiner

Date Considered: 5/14/04

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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P-0375.010-US

Applicant: KURT et al.

Appln. No.: 10/686,813

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Examiner: Rutledge	Group Art Unit: 1756	2851
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Date: February 20, 2004 Page

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Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR						
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		Document Number	Date MM/YYYY	Country	Inventor Name		Abstract		Readily Available	
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	SR									
	TR									
	UR									
	VR									
	WR									

D.R.	XR	SILVAST et al., "High-power plasma discharge source at 13.5 nm and 11.4 nm for EUV lithography," <i>Proc. SPIE</i> 3676:272-275 (1999)				
	YR					
	ZR					
	AAR					
	BBR					
	CCR					

Examin r

Date Considered: 5/14/04

PAT-144B 12/98